

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Koichi WATANABE et al.
Title: SPUTTERING TARGET AND PROCESS FOR PRODUCING
Si OXIDE FILM THEREWITH
Appl. No.: 10/573,406
International Filing Date: 09/22/2004
371(c) Date: 03/27/2006
Examiner: Jason Berman
Art Unit: 1795
Confirmation Number: 2973

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:


In response to the restriction requirement set forth in the Office Action mailed July 20, 2009, Applicant hereby provisionally elects Group I, Claims 1-3 and 10-11, for examination, without traverse.

Applicants reserve the right to file a divisional application covering the subject matter of the non-elected claims, and/or have additional claims considered in this application as appropriate.

Receipt of the initial Office Action on the merits is awaited.

Respectfully submitted,

Date August 19, 2009

By 

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